

ABSTRACT

A method for manufacturing a magnetic-disk substrate with which microwaviness having a wavelength of 50 to 200 μm can be reduced includes
5 polishing processing in which the substrate is sandwiched between a pair of polishing pads, a slurry containing polishing abrasive particles is supplied between the polishing pads and the substrate, and both main surfaces of the substrate are polished by sliding the polishing pads and the substrate relative to each other. Polishing surfaces of the polishing pads are made of a resin
10 foam material that has undergone opening formation processing before the polishing processing is performed on the substrate, the opening formation processing being processing in which openings are formed by shaving at least a surface film of the resin foam material. A resin foam material having, among surface roughnesses of the surface film of the resin foam material, an
15 arithmetic average roughness R_a of 0.65 μm or less before the opening formation processing is used as the raw material for the polishing pads that has not undergone the opening formation processing.

FIG. 3